

In the Specification

Please insert the following heading directly below the title on page 1:

--TECHNICAL FIELD--

Please amend the first paragraph on page 1, beginning at line 6, as follows:

--The invention relates to a polymerizable composition for the production of a resist, as ~~claimed in the precharacterizing clause of claim 1~~, a polymer prepared by polymerization, as ~~claimed in claim 6~~, a resist as ~~claimed in claim 7~~ and a lithography process as ~~claimed in the precharacterizing clause of claim 11~~.--

Please insert the following between the first and second paragraphs on page 1:

--BACKGROUND--

Please amend the second paragraph on page 1, beginning at line 11, as follows:

--Photomasks as used in semiconductor lithography currently generally consist of a transparent quartz glass plate on which a structured, nontransparent chromium layer is applied (COG: chrome on glass). In the production process, so-called mask blanks are used for this ~~purpose; these~~ purpose. These are quartz glass plates whose surface is completely covered with a continuous chromium layer which at present is from about 30 to 100 nm thick.--

Please amend the fourth paragraph on page 1, beginning at line 29, as follows:

--A relief-like image of the previously recorded structure results in the ~~resist~~; the resist. The resist protects the chromium layer in defined parts (the previously exposed or unexposed

parts, depending on the resist system), whereas the chromium between these parts is bare and can be further treated in a specific manner.--

Please insert the following between the second and third paragraphs on page 3, between lines 27 and 28:

--SUMMARY--

Please amend the last paragraph on page 3, beginning at line 36, as follows:

--This object is achieved, according to the invention, by a polymerizable composition for the production of a resist, comprising at least one unsaturated, polymerizable monomer having at least one silicon atom and at least one carbonyl group~~resist having the features of claim 1.~~--

Please insert the following after the last paragraph on page 4:

--BRIEF DESCRIPTION OF THE DRAWINGS:

For a more complete understanding of the present invention, and the advantages thereof, reference is now made to the following descriptions taken in conjunction with the accompanying drawing, in which:

Fig. 1 shows the general formula of a first embodiment monomer; and

Fig. 2 shows the general formula of a second embodiment monomer.--

Please insert the following before the first paragraph on page 5:

--DETAILED DESCRIPTION OF THE ILLUSTRATIVE EMBODIMENTS--

Please amend the last paragraph on page 7, beginning at line 14, as follows:

--When carried out, the invention is not limited to the abovementioned preferred working examples. Rather, a number of variants which make use of the [[The]] polymerizable composition as claimed in the invention, the polymer, the resist and the lithography process also in embodiments of basically different types is conceivable.--